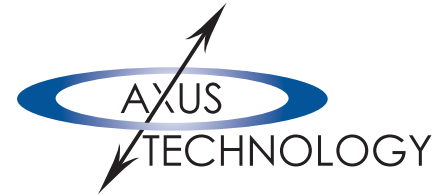


# Slurry Blend & Delivery System SDS-102 Series



Your source for leading-edge  
surface processing solutions



Axus Technology offers a wide variety of Slurry Blend and Delivery Systems, from basic systems for feeding one CMP polisher such as in a university or an R&D environment, to multiple-tank systems for larger, multiple polisher installations. Basic temperature control systems for maintaining consistent ambient conditions or for applications which require either elevated slurry temperature or reduced temperature slurry, are available options. Slurries are kept in suspension by propeller driven agitators or by magnetic levitation pumping systems. The Axus Technology slurry systems are adaptable to both high pH and low pH slurry formulations.

For automated point-of-use blending and delivery systems for multiple slurry types and components, please ask about the Axus Technology Gemini-2.

## FEATURES

- Systems available from basic systems to multi-tank automatic blending systems to facilitate any sized CMP polisher installed base
- Built-in agitation systems to assure slurry suspension
- Optional temperature control systems to enhance process consistency
- Systems are available with magnetic levitation suspension pumps to minimize particle generation
- Adaptable to both high pH and low pH polishing slurries
- Optional stainless steel platforms with easy-roll casters



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Slurry Rev 01 09 19

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Standard Features/Benefits	
Electrical connection to the CMP tool	Specific connections are included based upon the model number of the CMP tool to which it will be connected including either 110 volt or 230 volt systems.
Plumbing connection to the CMP tool	Includes plumbing and quick disconnect fittings for direct connection to specified CMP tools.
In-tank agitation with stainless steel propeller	Mixes slurry and keeps it in suspension; minimizes slurry settling for improved wafer-to-wafer slurry delivery consistency.
Low level sensor built into reservoir	Indicates to the operator that the slurry level is low, and refilling will be required soon.
Diaphragm feed pump	Standard pump for basic systems.
Gallon capacity	The systems are available in 5-gallon (19 liters), 15-gallon (56 liters), and 30-gallon (113 liters) tank capacities, tanks have tapered bottom.
Recirculating pump	Provides for consistent slurry head pressure to the polisher from where the desired quantity is drawn.
pH resistant holding/mixing tank	Polyethylene tank to resist high pH and low pH slurries.
Caster mounting platform	Stainless steel mounting platform on casters for easy move-about capability.

Optional Features/Benefits	
Slurry temperature control	Heating and/or cooling systems to provide consistent POU slurry temperature.
Auto refill	Automatic refill so the system can be connected to a remote slurry day-tank reservoir. Tank refills based upon low-level signal from sensor built into the holding tank.
Sealable for pressurized N2	To minimize drying within the reservoir, this option seals the tank lid and fittings to control the N2 pressure.
Magnetic levitating feed pump with integrated flow controller	Designed to generate fewer particulates during slurry pumping.
Multi-tank configurations	A 3-tank system, each with 5-gallon capacity, for mixing multiple component slurries near the point of use.

